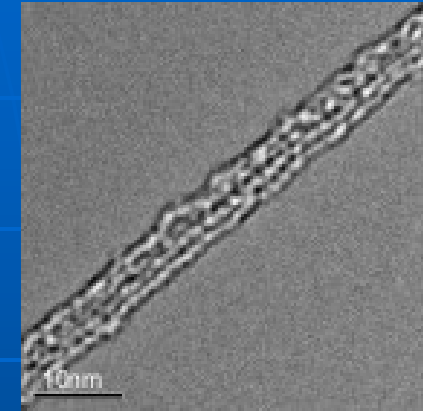


Si & Ge Nanoelectronics

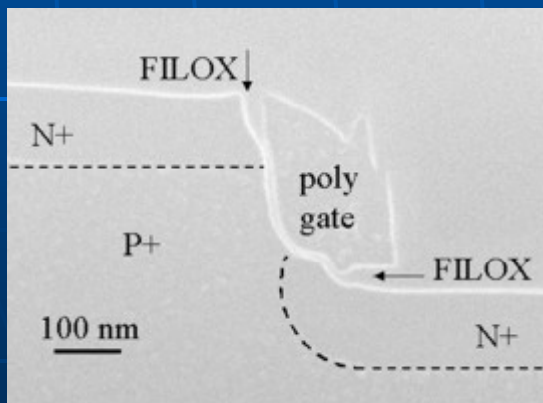
Kees de Groot, Associate Professor, University of Southampton

chdg@ecs.soton.ac.uk

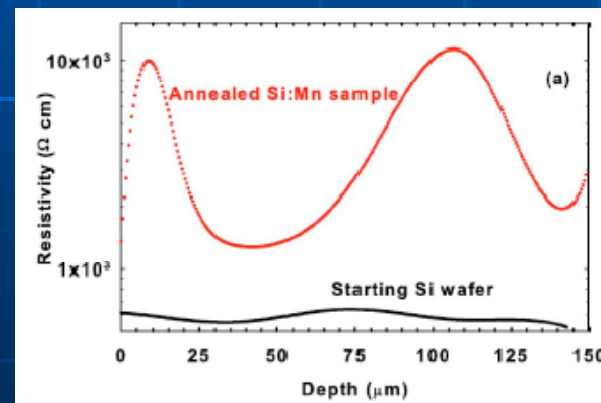
- Metal-free catalytic growth of Carbon nanotubes
 - Use of CVD or implanted Ge dots as seeds
- Novel MOSFET Device Architecture
 - Vertical MOSFETs, tunnel transistors
- Semi-Insulating Si for RF applications
 - Use of deep level dopants such as Mn



Ge catalyzed single wall CNT's



Vertical MOSFET with reduced parasitic capacitance

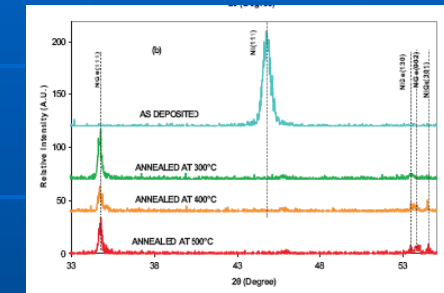


10 kOhmcm wafer resistivity with Mn deep level doping

Si & Ge Nanoelectronics

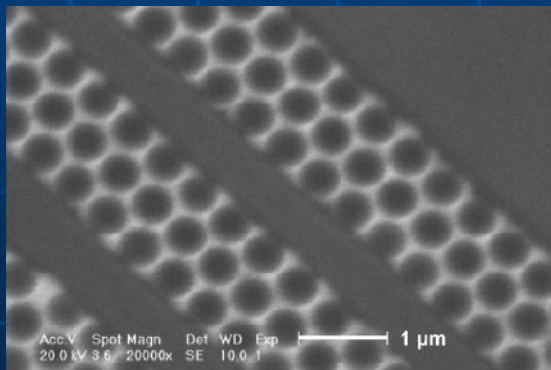
Applications of electro-deposition on Si and Ge

- N-type (heavily) doped Si & Ge used as electrode
- Low temperature process & selective growth
 - Low reverse “leakage” Schottky barrier
 - Spin injection Ni-Ge
 - Schottky barrier MOSFET NiGe-Ge
- Not a line of sight technique
 - Self assembly for magnetic data storage
 - Self assembly for plasmon waveguides

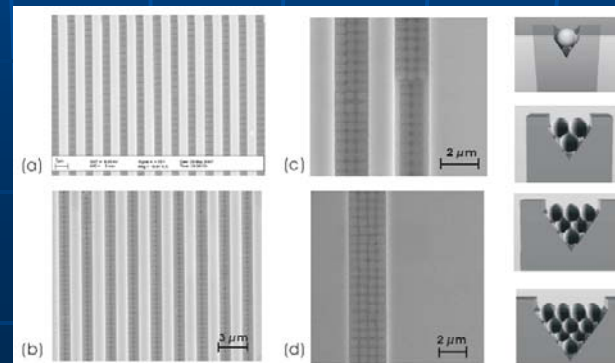


XRD of Ni-NiGe transformation

Self assembled latex spheres used as template for electrodeposited metals



HF etched square trenches



KOH etched v-grooves

Southampton Nanofabrication-centre

Opening December 2008

- **Lithography**
 - E-beam direct write: JEOL JBX 9300 FS
 - Aligner-Bonder: EVG602TBR (robotic)
 - FIB/SEM: FEI Helios Nanolab or Zeiss
 - He ion microscope: Zeiss Orion
 - Field Emission SEM: JEOL JSM 75000F
- **Deposition and Etch**
 - Epitaxy: ASM Epsilon
 - Nanowire: OPT Nanofab 100
 - Atomic layer deposition: OPT FlexAI RPX
 - Sputterer : Leybold Helios and OPT IonFab 300plus
 - Evaporator: Leybold LAB700
 - PECVD and ICP: STS LPX Pegasus and 4 OPT System100
- **Characterisation:**
 - Electrical: Cascade Summit 12000B with Agilent 70GHz RF , B1500A
 - Cryogenic/Magnetic: Elliot Lakeshore EMTTP4 and Cryogenic 300mK Cryogen Free
 - Scanning Probe Microscopes, low T AFM with tip enhanced Raman
 - Woolam M200V Ellipsometer and N&K 1700 RT Analyzer, Sula DLTS

